

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

Application Serial No. .... 10/733,201  
Filing Date ..... December 9, 2003  
Confirmation No. .... 5994  
Inventor ..... Garo J. Derderian et al.  
Assignee ..... Micron Technology, Inc.  
Group Art Unit ..... 1762  
Examiner ..... Kelly M. Stouffer  
Attorney's Docket No. .... MI22-2402  
Customer No. .... 021567  
Title: Atomic Layer Deposition Method of Depositing an Oxide on a Substrate

**RESPONSE TO JANUARY 18, 2008 OFFICE ACTION**

To: Mail Stop Amendment  
Commissioner for Patents  
P. O. Box 1450  
Alexandria, VA 22313-1450

From: Mark S. Matkin (Tel. 509-624-4276; Fax 509-838-3424)  
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Responsive to the Office Action dated January 18, 2008, Applicant amends  
and remarks as follows:

**AMENDMENTS**